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Application No.: 09/824,931

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T-779 P.002/004 F-809

AUG 05 2004

OFFICIAL

PATENT

Attorney Docket No. 3381

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Mittmann et al.

Examiner: Ardin H. Marschel

Serial No: 09/824,931

Group Art Unit: 1631

Filing Date: 4/3/01

Title: Photolithographic Method and
System for Efficient Mask Usage in
Manufacturing DNA Arrays

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INTERVIEW SUMMARY UNDER 37 C.F.R. 1.133

Dear Examiner Marschel:

This Interview Summary is hereby submitted in connection with the personal interview held on July 20, 2004, in regard to the above-referenced application. In attendance were Applicant's representatives William R. McCarthy III, and Philip L. McGarrigle, and Examiner Ardin H. Marschel.

Applicants wish to thank the Examiner for conducting the above interview to discuss the present invention. During the interview, Applicant's representative, Mr. McCarthy, described the invention with respect to a Response filed July 1, 2004 to the Office Action mailed January 5, 2004.

Specifically, Mr. McCarthy argued that that the reference (Hess et al. US 2002/0094533) applied with respect to the rejection to Claims 1-16 under 35 USC 102 (e) (1) does not teach the limitations required by the claims, in particular the subdivision of a mask into reticle areas, where each reticle area is further subdivided into reticles. Mr.

INT SUM. OK
AM 9-19-04